

	Hits	Search Text	DBs
34	2	356/636.ccls. and ((mitigat\$4 or reduc\$4 or decreas\$4 or monitor\$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER) same (line\$3dege\$3roughness or ((edge or side\$4) near12 roughnes\$4) or LER or (line\$3 near3 edge near4 roughnes\$3))) and (((trim\$4 near5 etch\$4) or trim\$5 or etch\$5) same (CD or (critical near5 dimension)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
35	2	716/19.ccls. and ((selective\$5 or response or signal\$4 or (defect near9 portion)) same (sensor or detect\$4 or interferomet\$4 or SEM) same (mitigat\$4 or reduc\$4 or decreas\$4 or monitor\$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER or post\$4heat\$4 or heat\$4) same (pattern or ((resist or photoresist or photosensitive)))) and ((trim\$6 or etch\$5 or CMP or PEB or post\$5bak or bak\$5 or correct\$4) same (asymmetr\$5 or deviat\$5 or varia\$5 or difference) same (pattern or profile or feature or CD or LER) same (photoresist or resist) same correct\$5) and gate	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
36	0	<pre> ((selective\$5 or response or signal\$4 or (defect near9 portion)) same (sensor or detect\$4 or interferomet\$4 or SEM) same (mitigat\$4 or reduc\$4 or decreas\$4 or monitor\$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER or post\$4heat\$4 or heat\$4) same (pattern or ((resist or photoresist or photosensitive)))) and ((trim\$6 or etch\$5 or CMP or PEB or post\$5bak or bak\$5) same (asymmetr\$5 or deviat\$5 or varia\$5 or difference) same (pattern or profile or feature or CD or LER) same (photoresist or resist) same correct\$5) and (monitor\$4 same (original or initial) same (photoresist or resist) same restor\$4 same trim\$4) </pre>	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
37	0	((selective\$5 or response or signal\$4 or (defect near9 portion)) same (sensor or detect\$4 or interferomet\$4 or SEM) same (mitigat\$4 or reduc\$4 or decreas\$4 or monitor\$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER or post\$4heat\$4 or heat\$4) same (pattern or ((resist or photoresist or photosensitive)))) and ((trim\$6 or etch\$5 or CMP or PEB or post\$5bak or bak\$5) same (asymmetr\$5 or deviat\$5 or varia\$5 or difference) same (pattern or profile or feature or CD or LER) same (photoresist or resist) same correct\$5) and (monitor\$4 same (original or initial) same (photoresist or resist) same restor\$4 same trim\$4)	US-PGPUB
38	30	430/322.ccls. and ((mitigat\$4 or reduc\$4 or decreas\$4 or monitor\$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER) same (line\$3dege\$3roughness or ((edge or side\$4) near12 roughnes\$4) or LER or (line\$3 near3 edge near4 roughnes\$3) or (photoresist near4 profile))) and (((trim\$4 near5 etch\$4) or trim\$5 or etch\$5) same (CD or (critical near5 dimension)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
39	2	430/320.ccls. and ((mitigat\$4 or reduc\$4 or decreas\$4 or monitor\$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER) same (line\$3dege\$3roughness or ((edge or side\$4) near12 roughnes\$4) or LER or (line\$3 near3 edge near4 roughnes\$3) or (photoresist near4 profile))) and (((trim\$4 near5 etch\$4) or trim\$5 or etch\$5) same (CD or (critical near5 dimension)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
40	0	356/237.1.ccls. and ((mitigat\$4 or reduc\$4 or decreas\$4 or monitor\$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER) same (line\$3dege\$3roughness or ((edge or side\$4) near12 roughnes\$4) or LER or (line\$3 near3 edge near4 roughnes\$3) or (photoresist near5 profile))) and (((trim\$4 near5 etch\$4) or trim\$5 or etch\$5) same (CD or (critical near5 dimension)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
41	4	356/625.ccls. and ((mitigat\$4 or reduc\$4 or decreas\$4 or monitor\$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER) same (line\$3dege\$3roughness or ((edge or side\$4) near12 roughnes\$4) or (photoresist near4 profile) or LER or (line\$3 near3 edge near4 roughnes\$3))) and (((trim\$4 near5 etch\$4) or trim\$5 or etch\$5) same (CD or (critical near5 dimension)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
42	9	356/601.ccls. and ((mitigat\$4 or reduc\$4 or decreas\$4 or monitor\$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER) same (line\$3dege\$3roughness or ((edge or side\$4) near12 roughnes\$4) or LER or (profile near6 photoresist) or (line\$3 near3 edge near4 roughnes\$3))) and (((trim\$4 near5 etch\$4) or trim\$5 or etch\$5) same (CD or (critical near5 dimension)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
43	0	((selective\$5 or response or signal\$4 or (defect near9 portion)) same (sensor or detect\$4 or interferomet\$4 or SEM) same (mitigat\$4 or reduc\$4 or decreas\$4 or monitor\$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER or post\$4heat\$4 or heat\$4) same (pattern or ((resist or photoresist or photosensitive)))) and (((trim\$6 US-PGPUB or etch\$5 or CMP or PEB or post\$5bak or bak\$5) same (asymmetr\$5 or deviat\$5 or varia\$5 or difference) same (pattern or profile or feature or CD or LER) same (photoresist or resist) same correct\$5) and (monitor\$4 same (original or initial) same (photoresist or resist) same restor\$4 same trim\$4)	

	Hits	Search Text	DBs
44	2	430/311.ccls. and ((selective\$5 or response or signal\$4 or (defect near9 portion)) same (sensor or detect\$4 or interferomet\$4 or SEM) same (mitigat\$4 or reduc\$4 or decreas\$4 or monitor\$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER or post\$4heat\$4 or heat\$4) same (pattern or ((resist or photoresist or photosensitive)))) and ((trim\$6 or etch\$5 or CMP or PEB or post\$5bak or bak\$5 or correct\$4) same (asymmetr\$5 or deviat\$5 or varia\$5 or difference) same (pattern or profile or feature or CD or LER) same (photoresist or resist) same correct\$5) and gate	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
45	1	430/330.ccls. and ((selective\$5 or response or signal\$4 or (defect near9 portion)) same (sensor or detect\$4 or interferomet\$4 or SEM) same (mitigat\$4 or reduc\$4 or decreas\$4 or monitor\$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER or post\$4heat\$4 or heat\$4) same (pattern or ((resist or photoresist or photosensitive)))) and ((trim\$6 or etch\$5 or CMP or PEB or post\$5bak or bak\$5 or correct\$4) same (asymmetr\$5 or deviat\$5 or varia\$5 or difference) same (pattern or profile or feature or CD or LER) same (photoresist or resist) same correct\$5) and gate	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
46	7	430/30.ccls. and ((selective\$5 or response or signal\$4 or (defect near9 portion)) same (sensor or detect\$4 or interferomet\$4 or SEM) same (mitigat\$4 or reduc\$4 or decreas\$4 or monitor\$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER or post\$4heat\$4 or heat\$4) same (pattern or ((resist or photoresist or photosensitive)))) and ((trim\$6 or etch\$5 or CMP or PEB or post\$5bak or bak\$5 or correct\$4) same (asymmetr\$5 or deviat\$5 or varia\$5 or difference) same (pattern or profile or feature or CD or LER) same (photoresist or resist) same correct\$5) and gate	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
47	0	356/637.ccls. and ((mitigat\$4 or reduc\$4 or decreas\$4 or monitor\$4 or reflow or (thermal near5 reflow) or RELACS or SAFIER) same (line\$3dege\$3roughness or ((edge or side\$4) near12 roughnes\$4) or LER or (line\$3 near3 edge near4 roughnes\$3) or (photoresist near5 profile))) and (((trim\$4 near5 etch\$4) or trim\$5 or etch\$5) same (CD or (critical near5 dimension)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB